

Lawrence Berkeley National Laboratory

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International Workshop on EUV Lithography

June 14, 2017



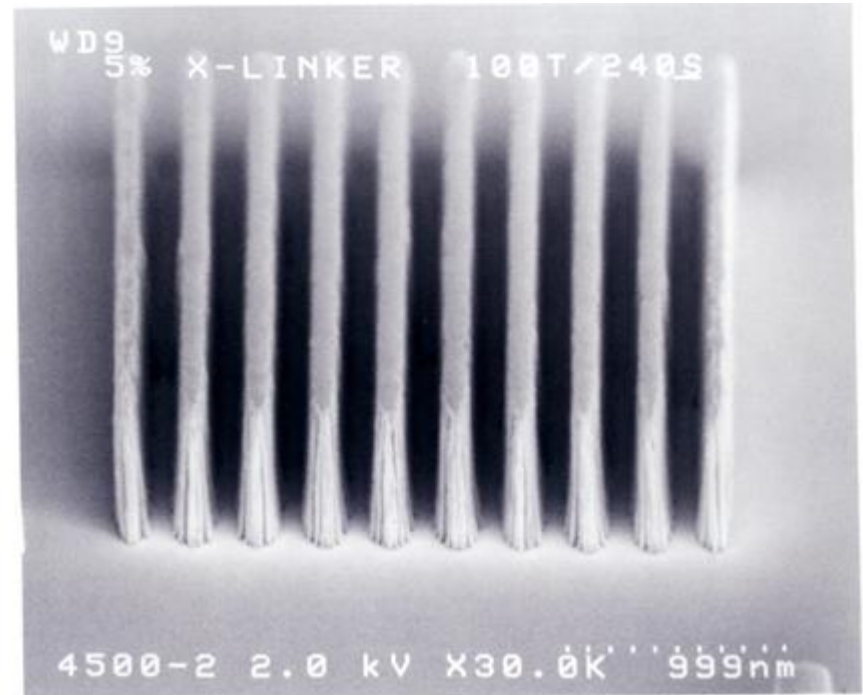
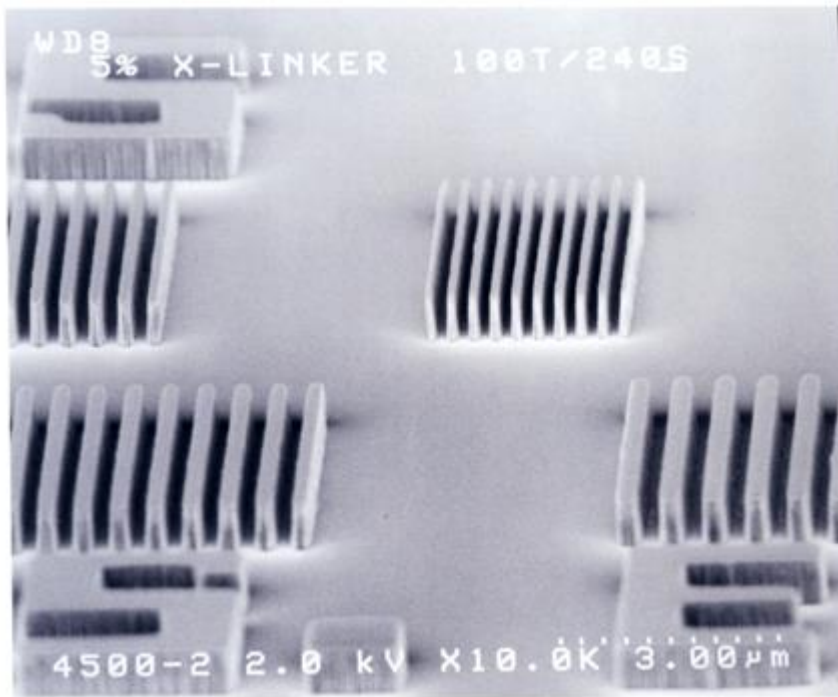
Thank you for building on 25 years of EUVL progress!

First Japan-U.S. workshop on EUV Lithography, October, 1993



Top-surface imaging results from laser-plasma illuminated AT&T/Sandia Schwartzschild 10x camera (April, 1996)

Exposed and silylated at Sandia/CA, etched at Intel/Santa Clara



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